

Manufacturing and Industrialization of EUV Lithography Optics

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The evolution of the optics by Carl Zeiss for the EUV Lithography tools by ASML is shown. We demonstrate which performance improvements in wavefront, flare and transmission have been achieved over the past decades. We emphasize the importance of closed-loop process control and the essential role of appropriate metrology for individual mirrors as well as for the entire illumination system and projection optics.